Notice of Allowability	Application No.	Applicant(s)	
	10/082,576	AOYAMA, JUNICHI	
	Examiner	Art Unit	
	Shouxiang Hu	2811	
The MAILING DATE of this communication apperall claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED or other appropriate comr GHTS. This application is and MPEP 1308.	in this application. If not included nunication will be mailed in due course	
<ol> <li>This communication is responsive to <u>08-27-04 amendment</u></li> </ol>	,		
2. X The allowed claim(s) is/are <u>1-6,8-15 and 17-19</u> .			
3. $igotimes$ The drawings filed on <u>25 February 2002</u> are accepted by the	ne Examiner.		
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority unall a)  All b)  Some* c)  None of the:</li> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> <li>3.  Copies of the certified copies of the priority documents</li> </ul>	been received. been received in Applicate	ion No	om the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:  Applicant has THREE MONTHS FROM THE "MAILING DATE"	of this communication to f	le a reply complying with the requirem	ents
noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.			
<ol> <li>A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give</li> </ol>			OF
<ol> <li>CORRECTED DRAWINGS ( as "replacement sheets") mus</li> </ol>	•		
(a) including changes required by the Notice of Draftspers	on's Patent Drawing Revi	ew ( PTO-948) attached	
1) hereto or 2) to Paper No./Mail Date			
(b) including changes required by the attached Examiner's Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the			of
<ol> <li>DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT</li> </ol>			е
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5 Notice of	Informal Patent Application (PTO-152)	
2. ☐ Notice of Preferences Cited (P10-692)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)		Summary (PTO-413),	
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0		o./Mail Date <u>20041110</u> . 's Amendment/Comment	
Paper No./Mail Date	•		
<ol> <li>Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ol>	8.	s Statement of Reasons for Allowance	9
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U.S. Patent and Trademark Office		5 11 E 3 Sec. 17	

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04)

## **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Christopher P. Rauch (RN: 45,034) on November 04, 2004.

The application has been amended as follows:

## IN THE CLAIMS

- 1. Claims 7, 16 and 20-40 are canceled.
- Claims 1 and 10 are amended as following:

Claim 1. (currently amended) A semiconductor device in which a second conductive layer is connected through a connection pillar to a first conductive layer embedded in a groove formed in an insulation film, wherein:

said connection pillar is formed directly on a surface of said first conductive layer and exhibits a crystallographical alignment to the first conductive layer and a mechanical strength effected by being grown from the surface of the first conductive layer without use of a <u>any</u> growth guide at a direction of a width of the first conductive layer such that the connection pillar has a width that is <u>self-aligned</u> to the width of the first conductive layer without use of the <u>any</u> growth guide, and

said second conductive layer is formed on a surface of the connection pillar opposite the first conductive layer.

Claim 10. (currently amended) A semiconductor device in which a second conductive layer is connected through a connection pillar to a first conductive layer embedded in a groove formed in an insulation film, wherein:

a growth suppression film formed on said insulation film and said first conductive layer, the growth suppression film having an opening formed through an entire thickness thereof, the opening positioned across a width of the first conductive layer and having a width that is wider than the width of the first conductive layer, and

said connection pillar is formed directly on a surface of said first conductive layer within said opening of said growth suppression film and exhibits a crystallographical alignment to the first conductive layer and a mechanical strength effected by being grown from the surface of the first conductive layer without use of a <u>any</u> growth guide at a direction of the width of the first conductive layer such that the connection pillar has a width that is <u>self-aligned</u> to the width of the first conductive layer without use of the <u>any</u> growth guide, and

said second conductive layer is formed on a surface of the connection pillar opposite the first conductive layer.

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Allowable Subject Matter

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Claims 1-6, 8-15 and 17-19 are allowed.

Conclusion

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Shouxiang Hu whose telephone number is 571-272-

1654. The examiner can normally be reached on Monday through Thursday, 7:30 AM

to 6:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Eddie C. Lee can be reached on 571-272-1732. The fax phone number for

the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the

Patent Application Information Retrieval (PAIR) system. Status information for

published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only.

For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

SH

November 11, 2004

SHOUXIANG HU PRIMARY EXAMINE